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Ryu OHTAGURO, et al. 10/808,540 Substrate For Photomask, Photomask Blank and Photomask Filing Date: March 25, 2004 Darryl Mexic 202-663-7909 1 0f 3

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FIG. 1A

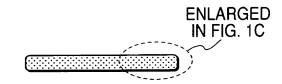


FIG. 1B

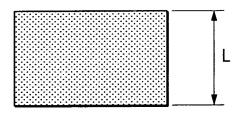


FIG. 1C

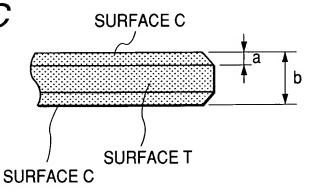
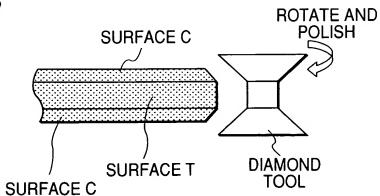
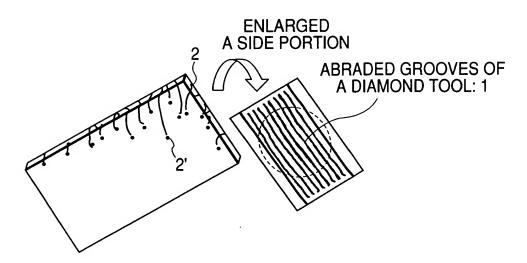


FIG. 2



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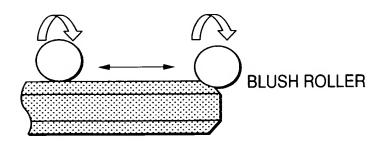
FIG. 3



(MOVING DISPLAYS ARE ALL PARTICLE)

FIG. 4

SWAY WITH ROTATING



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FIG. 5

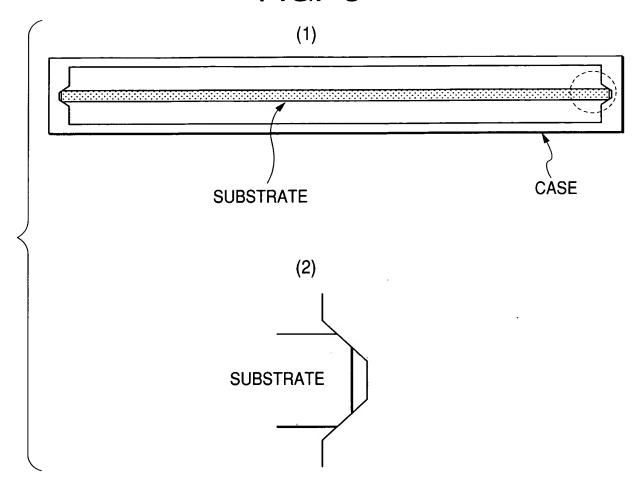


FIG. 6

